

Abstract Submitted
for the GEC11 Meeting of
The American Physical Society

Semi-analytical sheath model for electronegative radio frequency plasmas DEUK-CHUL KWON, National Fusion Research Institute, HYONU CHANG, JUNG-SIK YOON — In plasma etching processes, the ion energy distributions (IEDs) arriving at substrates strongly affect the etching rates. In order to accurately determine the IEDs, various analytic and numerical models have been developed. However, over the past few decades, very few studies have been conducted on sheath model for electronegative radio frequency plasmas. Therefore, in this work, an equivalent circuit model is presented for electronegative radio frequency plasmas.

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Date submitted: 15 Jul 2011

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